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ning of each regular issue of the PCT Gazette.

(54) Title: ORGANIC SILICATE POLYMER AND INSULATION FILM COMPRISING THE SAME

(57) Abstract: The present invention relates to an organic silicate polymer prepared by mixing silane compound with organic sol-
vent to prepare a first mixture, and hydrolyzing and condensing the first mixture by adding water and catalyst, the first mixture being
selected from a group consisting of oxidized hydrosilane, cyclic siloxane, a second mixture of oxidized hydrosilane and silane or
silane oligomer, and a third mixture of cyclic siloxane and silane or silane oligomer, a composition for forming an insulation film of
semiconductor devices prepared by using the organic silicate polymer, a method for preparing an insulation film using the compo-
sition, and a semiconductor device comprising the insulation film.

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